

Title (en)

ARRANGEMENT UND METHOD FOR THE GRADUAL SHUTOFF OF POTENTIAL IN HIGH VOLTAGE TECHNOLOGY

Title (de)

ANORDNUNG UND VERFAHREN ZUR POTENTIALABSTEUERUNG IN DER HOCHSPANNUNGSTECHNIK

Title (fr)

AGENCEMENT ET PROCÉDÉ DE DÉCHARGE DE POTENTIEL DANS LA TECHNIQUE LIÉE AUX HAUTES TENSIONS

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Application

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Abstract (en)

[origin: WO2020048720A1] The invention relates to an arrangement (27) and to a method for the gradual shutoff of potential in high voltage technology, comprising at least one armature body (28), electrically insulating film (29), and electrically conductive regions (4), wherein the electrically conductive regions (4) are arranged between layers of the electrically insulating films (29), and at least parts of the electrically insulating film (29) are arranged around the at least one armature body (28). The arrangement (27) is designed for direct current applications, wherein resistive compensation currents are reduced and/or avoided along the electrically insulating film (29) by configuration for higher voltage levels, and/or by an armature body (28), which functions as a first gradual potential shutoff coating, and/or by means of the electrical contacting of the outermost electrically conductive region (4) between layers of electrically insulating film (29) via an electrical contact (30) through an opening (31) in the outer layer of the insulating film (29).

IPC 8 full level

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